

<b>Notice of References Cited</b>	Application/Control No. 10/783,034	Applicant(s)/Patent Under Reexamination PELLENS, RUDY JAN MARIA	
	Examiner Kevin Quinto	Art Unit 2826	Page 1 of 1

**U.S. PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
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**NON-PATENT DOCUMENTS**

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Malik et al., "Polymer Structural Variation Towards Enhancing KrF Resist Lithographic Properties," Journal of Photopolymer Science and Technology, 1998, Vol. 11, No. 3, p. 431-438
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